

IN THE CLAIMS

1 - 13 (Cancelled)

14. (Previously Presented): Glazing comprising a glass substrate coated with a layer of aluminium oxynitride deposited by gas-phase pyrolysis, the thickness and refractive index characteristics thereof being selected so as to attenuate the reflected colours produced by an oxide layer providing the glazing with low-emission and/or solar protection properties, said layer being deposited onto the aluminium oxynitride layer.

15. (Currently Amended): Glazing according to Claim ~~[[1]]~~ 14, and including at least one of the following features (A) through (D);

B1 (A) wherein the constituent elements of the aluminium oxynitride layer are respectively in the following atomic proportions:

Al from 40 to 50%

N from 20 to 50%

O from 10 to 60%;

(B) wherein the reflective index of the aluminium oxynitride layer is in the range of between 1.6 and 1.8;

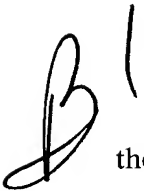
(C) wherein the thickness of the aluminium oxynitride layer is in the range of between 500 and 900 ångströms; and

(D) wherein the oxide layer providing the low-emission and/or solar protection properties is a layer based on doped tin oxide.

16. (Previously Presented): Glazing according to Claim 15 and including at least two of the features (A) through (D).

17. (Previously Presented): Glazing according to Claim 15 and including all of the features (A) through (D).

18. (Previously Presented): Glazing according to Claim 17 wherein:
the constituent elements of the aluminium oxynitride layer are respectively in the following atomic proportions:



Al	from 45 to 50%
N	from 22 to 30%
O	from 20 to 27%;

the refractive index of the aluminium oxynitride layer is in the range of between 1.65 and 1.75;
and

the aluminium oxynitride layer has a thickness in the range of between 650 and 850 ångströms.

19. (Previously Presented): Glazing according to Claim 14 wherein the oxide layer providing the low-emission and/or solar protection properties is a layer based on at least one of the following (E) through (G):

(E) doped tin oxide;

(F) is a tin oxide layer containing antimony oxide, the atomic ratio Sb/Sn being in the range of between 0.02 and 0.15;

(G) fluorine-doped tin oxide.

20. (Previously Presented): Process for the production of glazing according to Claim 14, wherein the aluminium oxynitride layer is formed by pyrolysis using gaseous precursors comprising aluminium trichloride or trimethyl aluminium.

21. (Previously Presented): Process for the production of glazing according to Claim 20, wherein the gaseous precursors also comprise ammonia.

22. (Previously Presented): Process for the production of glazing according to Claim 20,
wherein the aluminium precursor is aluminium trichloride, the precursors also contain water
vapour.

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